

EV317135795

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. .... 10/039,456  
Priority Filing Date .... December 31, 2001  
Inventor .... Ying Huang et al.  
Assignee .... Micron Technology, Inc.  
Priority Group Art Unit .... 2829  
Priority Examiner .... S.B. Geyer  
Attorney's Docket No. .... MI22-2347  
Title: An Improved Method, Structure and Process Flow to Reduce Line-Line Capacitance  
with Low-K Material

**INFORMATION DISCLOSURE STATEMENT**

References - - See attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449.


No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 10/039,456, filed December 31, 2001, upon which the above-identified application relies for a priority date under 35 U.S.C. §120. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Date: 7-23-03

  
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D. Brent Kenady  
Reg. No. 40,045



Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2347		Priority SERIAL NO. 10/039,456		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Ying Huang et al.				
				FILING DATE		GROUP		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,946,601	8/99	Wong et al.				
	AB	6,033,979	3/00	Endo				
	AC	6,037,664	3/00	Zhao et al.				
	AD	6,046,104	4/00	Kepler				
	AE	6,057,417	5/00	Arnold et al.				
	AF	6,284,657 B1	09/01	Chooi et al.				
	AG	5,122,483	06/92	Sakai et al.				
	AH	6,265,779 B1	07/01	Grill et al.				
	AI	6,410,437 B1	06/25/02	Flanner et al.				
	AJ							
	AK							
	AL							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Baliga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-6					
	AS		Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5					
	AT							
EXAMINER				DATE CONSIDERED				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								